
**Microbeam analysis — Electron probe
microanalysis (EPMA) — Vocabulary**

*Analyse par microfaisceaux — Analyse par microsonde électronique
(microsonde de Castaing) — Vocabulaire*

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Published in Switzerland

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Foreword

ISO (the International Organization for Standardization) is a worldwide federation of national standards bodies (ISO member bodies). The work of preparing International Standards is normally carried out through ISO technical committees. Each member body interested in a subject for which a technical committee has been established has the right to be represented on that committee. International organizations, governmental and non-governmental, in liaison with ISO, also take part in the work. ISO collaborates closely with the International Electrotechnical Commission (IEC) on all matters of electrotechnical standardization.

International Standards are drafted in accordance with the rules given in the ISO/IEC Directives, Part 2.

The main task of technical committees is to prepare International Standards. Draft International Standards adopted by the technical committees are circulated to the member bodies for voting. Publication as an International Standard requires approval by at least 75 % of the member bodies casting a vote.

Attention is drawn to the possibility that some of the elements of this document may be the subject of patent rights. ISO shall not be held responsible for identifying any or all such patent rights.

ISO 23833 was prepared by Technical Committee ISO/TC 202, *Microbeam analysis*, Subcommittee SC 1, *Terminology*.

The European Microbeam Analysis Society (EMAS) made contributions to the preparation of the document.

This second edition of ISO 23833 cancels and replaces the first edition (ISO 23833:2006), of which it constitutes a minor revision.

This International Standard has a cross-reference relationship with the surface chemical analysis vocabulary prepared by ISO/TC 201 (ISO 18115-1:2010).

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Introduction

Electron probe X-ray microanalysis (EPMA) is a modern technique used to qualitatively determine and quantitatively measure the elemental composition of solid materials, including metal alloys, ceramics, glasses, minerals, polymers, powders, etc., on a spatial scale of approximately one micrometer laterally and in depth. EPMA is based on the physical mechanism of electron-stimulated X-ray emission and X-ray spectrometry.

As a major sub-field of microbeam analysis (MBA), the EPMA technique is widely applied in diverse business sectors (high-tech industries, basic industries, metallurgy and geology, biology and medicine, environmental protection, trade, etc.) and has a wide business environment for standardization.

Standardization of terminology in a technical field is one of the basic prerequisites for development of standards on other aspects of that field.

This International Standard is relevant to the need for an EPMA vocabulary that contains consistent definitions of terms as they are used in the practice of electron probe microanalysis by the international scientific and engineering communities that employ the technique.

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Microbeam analysis — Electron probe microanalysis (EPMA) — Vocabulary

1 Scope

This International Standard defines terms used in the practices of electron probe microanalysis (EPMA). It covers both general and specific concepts classified according to their hierarchy in a systematic order.

This International Standard is applicable to all standardization documents relevant to the practices of EPMA. In addition, some parts of this International Standard are applicable to those documents relevant to the practices of related fields (SEM, AEM, EDX, etc.) for definition of those terms common to them.

2 Abbreviated terms

| | |
|------|---|
| BSE | backscattered electron |
| CRM | certified reference material |
| EDS | energy-dispersive spectrometer |
| EDX | energy-dispersive X-ray spectrometry |
| EPMA | electron probe microanalysis or electron probe microanalyser |
| eV | electronvolt ISO 23833:2013 |
| keV | kiloelectronvolt https://standards.iteh.ai/catalog/standards/sist/5bbc47dc-660b-4b24-9e3d-acd4777439a3/iso-23833-2013 |
| RM | reference material |
| SE | secondary electron |
| SEM | scanning electron microscope |
| WDS | wavelength-dispersive spectrometer |
| WDX | wavelength-dispersive X-ray spectrometry |

3 Definitions of general terms used in electron probe microanalysis

3.1

electron probe microanalysis

EPMA

technique of spatially-resolved elemental analysis based upon electron-excited X-ray spectrometry with a focussed electron probe and an electron interaction volume with micrometer to sub-micrometer dimensions

3.1.1

qualitative EPMA

procedure in EPMA leading to the identification of the elements present in the electron-excited interaction volume by a systematic method for the recognition and assignment of X-ray spectral peaks to specific elements

3.1.2

quantitative EPMA

procedure leading to the assignment of numerical values to represent the concentrations of elemental constituents that had been previously identified in the electron-excited interaction volume during the qualitative analysis phase in EPMA

Note 1 to entry: Quantitative analysis can be accomplished by comparing the unknown X-ray peak intensities to X-ray peak intensities measured under the same conditions using reference material(s) or by calculating the concentration from first principles (also known as standardless analysis).

3.2

electron probe microanalyser

instrument for carrying out electron-excited X-ray microanalysis

Note 1 to entry: This instrument is usually equipped with more than one wavelength spectrometer and an optical microscope for precise specimen placement.

3.3

electron scattering

deviation in trajectory and/or kinetic energy suffered by an impinging energetic beam electron as a result of an interaction with a specimen atom or electron

3.3.1

angle of scattering

scattering angle

angle between the direction of the incident particle or photon and the direction that the particle or photon is traveling after scattering

[ISO 18115-1:2010]

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3.3.2

backscattering

escape of beam electrons from the specimen following sufficient scattering events to cause the trajectories to intersect the entrance surface of the specimen

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3.3.2.1

backscatter coefficient

η

fraction of beam electrons that are backscattered, given by the equation

$$\eta = n(\text{BS})/n(\text{B})$$

where $n(\text{B})$ is the number of incident electrons and $n(\text{BS})$ is the number of backscattered electrons

3.3.2.2

backscattered electron

electron ejected from the entrance surface of the specimen by a backscattering process

3.3.2.3

backscattered electron angular distribution

distribution of backscattered electrons as a function of the angle relative to the surface normal

3.3.2.4

backscattered electron depth distribution

distribution of backscattered electrons as a function of the maximum depth into the specimen reached before travelling back to the entrance surface to exit the specimen

3.3.3**continuous energy loss approximation**

mathematical description of energy loss by fast electrons propagating through matter in which all of the discrete inelastic processes are approximated as a single continuous energy loss process

Note 1 to entry: Also known as the continuous slowing-down approximation (CSDA).

3.3.4**elastic scattering**

interaction of an energetic electron from the impinging beam and a specimen atom during which the electron's energy remains essentially unaltered but its trajectory is changed by an angle from 0 up to π rad (180°) with an average of approximately 0,1 rad

3.3.5**inelastic scattering**

interaction of an energetic electron from the impinging beam and a specimen atom or electron during which kinetic energy is lost to the specimen by various mechanisms (secondary electron generation, bremsstrahlung, inner shell ionization, plasmon and photon excitation)

Note 1 to entry: For inelastic scattering, the electron trajectory is modified by a small angle, generally less than 0,01 rad.

3.3.6**scattering cross-section**

number of scattering events per unit area

mathematical description of the probability of a scattering event (elastic or inelastic)

Note 1 to entry: See *ionization cross-section* (3.4.4).

Note 2 to entry: Scattering cross-section is usually expressed simply as an area, in cm^2 . The number of scattering events per unit area is expressed in events/(atoms/ cm^2).

3.3.7**scattering effect**

measurable physical phenomenon, such as electron backscattering or loss of X-ray generation, that results from modification of the trajectory and/or kinetic energy of an impinging energetic beam electron by scattering processes in the specimen

3.3.8**secondary electron**

Electron emitted from the specimen as a result of inelastic scattering of the primary beam electron by loosely bound valence-level electrons of the specimen

Note 1 to entry: Secondary electrons have conventionally an energy less than 50 eV.

3.4**X-ray**

photon of electromagnetic radiation created by fluorescence of an inner shell electron vacancy or by deceleration of an energetic electron in the Coulombic field of an atom

3.4.1**characteristic X-ray**

photon of electromagnetic radiation created by the relaxation of an excited atomic state created by inner shell ionization following inelastic scattering of an energetic electron or ion, or by absorption of an X-ray photon

3.4.2**continuous X-ray**

photon of electromagnetic radiation created by deceleration (an inelastic scattering mechanism) of an energetic electron in the Coulombic field of an atom

**3.4.3
fluorescence yield**

ω
fraction of inner shell ionization events that give rise to characteristic X-ray emission during subsequent de-excitation

Note 1 to entry: The fluorescence yield is independent of the method of ionization.

**3.4.4
ionization cross-section**

number of ionization events per unit area
mathematical description of the probability of ionizing an atom by removing an atomic electron from a particular bound electron shell into the unbound vacuum, or continuum, energy level or state

Note 1 to entry: See *scattering cross-section* (3.3.6).

Note 2 to entry: Ionization cross-section is usually expressed simply as an area, in cm^2 or in barns (10^{-24}cm^2). Ionization event probability is expressed in events/(atoms/ cm^2).

Note 3 to entry: Ionization cross-section is usually denoted by Q , which is defined by the mathematical expression $dn = Q(N\rho/A)dx$ where dn is the number of ionization events which occur in each increment dx of electron path and $N\rho/A$ is the number of atoms per unit volume.

**3.4.5
ionization energy**

critical excitation energy
edge energy
minimum energy required to ionize an atomic electron, i.e. to remove a bound electron from a shell (K, L, etc.) to (as a minimum) the continuum of energy states in a solid

Note 1 to entry: Ionization energy units are eV or keV.

**3.4.6
J-value**

mean ionization energy, a critical parameter in mathematical descriptions of the continuous energy loss approximation

**3.4.7
stopping power**

dE/ds
rate of energy loss experienced by a primary electron (from all inelastic scattering processes) with distance travelled in the specimen

Note 1 to entry: Stopping power is expressed as energy loss/unit distance (e.g. eV/nm).

**3.4.8
X-ray fluorescence effect
secondary fluorescence**

photoelectric absorption of an X-ray (characteristic or bremsstrahlung) by an atom, resulting in an excited atomic state which will de-excite with electron shell transitions and subsequent emission of an Auger electron or the characteristic X-ray of the absorbing atom

**3.4.9
X-ray generation**

generation of X-rays in the specimen under the stimulation of an incident beam of radiation (electrons, ions or photons)

Note 1 to entry: X-rays can be generated through the ionization of inner atomic shells (characteristic X-rays) or through the "braking radiation" (bremsstrahlung) process (continuum or white radiation).

3.5**X-ray absorption**

attenuation of the intensity of X-rays passing through matter, arising primarily from photoelectric absorption for X-ray energies appropriate to EPMA

3.5.1**absorption edge**

critical ionization energy for a particular shell or subshell of an atom species

Note 1 to entry: Absorption edges are detected in spectra as discontinuities in the X-ray continuum (bremsstrahlung) background due to a sharp change in the X-ray mass absorption coefficient at the edge.

3.5.2**absorption factor**
 $f(\chi)$

ratio of emitted X-ray intensity to the generated intensity in a specific direction towards the X-ray detector

3.5.3**depth distribution function**
 $\phi(\rho z)$

function which describes the distribution of generated X-rays as a function of depth below the specimen surface

Note 1 to entry: ρz is expressed in units of density \times thickness (depth).

3.5.4**jump ratio**

<EPMA, TXRF> ratio of the X-ray absorption coefficient at an energy just above an absorption edge to that at an energy just below the edge

Note 1 to entry: X-ray absorption spectra can have complex shapes for X-ray energies in the vicinity of photoionization thresholds, and a well-defined edge is not always observed at the threshold.

[ISO 18115-1:2010]

3.5.5**mass absorption coefficient**
 μ_1/ρ

material parameter that relates the loss of X-ray intensity due only to photoelectric absorption during passage through matter, where μ_1 is the linear absorption coefficient and ρ is the material density

Note 1 to entry: Its dimensions are area/mass (e.g. cm²/g). It is sometimes referred to as the mass absorption cross section.

3.5.6**mass attenuation coefficient**
 μ/ρ

material parameter that relates the loss of X-ray intensity due to all absorption and scattering processes during passage through matter, given by the equation

$$I/I_0 = \exp[-(\mu/\rho)\rho s]$$

where I_0 is the incident X-ray intensity, I is the intensity remaining after passage through a distance s of the material, μ is the linear attenuation coefficient, ρ is the material density, s is the path thickness in cm

Note 1 to entry: Its dimensions are area/mass (e.g. cm²/g). It is sometimes referred to as the mass attenuation cross section.

3.5.7

mass-depth distance

ρz
description of a dimension in terms of the product of linear distance (cm) and density (g/cm^3)

Note 1 to entry: It is expressed in grams per square centimetre.

3.5.8

X-ray take-off angle

ψ
angle between the specimen surface and the central axis of the X-ray spectrometer

3.6

X-ray spectrum

plot of the X-ray photon abundance as a function of the energy or wavelength

Note 1 to entry: Most often, the number of photons/unit time is plotted, but other measures of the intensity are possible.

3.6.1

characteristic X-ray spectrum

X-ray peaks or lines associated with a particular atom species and generated as a result of inner shell ionization (caused by an energetic electron, ion, or photon) followed by inter-shell electron transitions and emission of excess energy as a photon of electromagnetic radiation

3.6.1.1

family of X-ray lines

systematic set of characteristic X-rays produced as a result of all possible routes of ionization of a particular shell/subshell and the subsequent inter-shell electron transitions that occur

3.6.1.2

K-line

one of the characteristic line emissions following K-shell ionization

3.6.1.3

K-spectrum

series of characteristic X-rays arising from ionization of an electron bound in the K-shell of an atom

3.6.1.4

L-line

one of the characteristic line emissions following L-shell ionization

3.6.1.5

L-spectrum

series of characteristic X-rays arising from ionization of an electron bound in the L-shell of an atom

3.6.1.6

M-line

one of the characteristic line emissions following M-shell ionization

3.6.1.7

M-spectrum

series of characteristic X-rays arising from ionization of an electron bound in the M-shell of an atom

3.6.1.8

satellite line

low relative abundance feature near a characteristic peak that can result from any of a variety of processes or situations: "forbidden" transitions, "non-diagram" lines and doubly-ionized atoms